



April 3, 2002

To: Commissioner of Patents and Trademarks  
Washington, D.C. 20231

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TECHNOLOGY CENTER

Subject:

Serial No. 10/081,985 02/21/02

Zhi-Cherng Lu et al.

ADJUSTMENT OF N AND K VALUES IN  
A DARC FILM

Grp. Art Unit: 2812

## INFORMATION DISCLOSURE STATEMENT

Enclosed is Form PTO-1449, Information Disclosure Citation  
In An Application.


The following Patents and/or Publications are submitted to  
comply with the duty of disclosure under CFR 1.97-1.99 and  
37 CFR 1.56. Copies of each document is included herewith.

## CERTIFICATE OF MAILING

I hereby certify that this correspondence is being  
deposited with the United States Postal Service as first class  
mail in an envelope addressed to: Commissioner of Patents and  
Trademarks, Washington, D.C. 20231, on April 10, 2002.

Stephen B. Ackerman, Reg.# 37761

Signature/Date

 4/10/02

U.S. Patent 6,291,363 to Yin et al., "Surface Treatment of DARC Films to Reduce Defects in Subsequent Cap Layers," discloses an ammonia based treatment of a dielectric anti-reflective coating (DARC) layer to minimize formation of defects therein.

U.S. Patent 6,228,700 to Lee, "Method for Manufacturing Dynamic Random Access Memory," discloses a SION or SIOX DARC layer process.

U.S. Patent 6,063,704 to Demirlioglu, "Process for Incorporating Silicon Oxynitride DARC Layer into Formation of Silicide Polysilicon Contact," discloses a silicon oxynitride dielectric anti-reflective coating layer process wherein a DARC is given added silicon so that it can be used in a SALICIDE process.

U.S. Patent 6,060,132 to Lee, "High Density Plasma CVD Process for Making Dielectric Anti-reflective Coatings," discloses a chemical vapor deposition dielectric anti-reflective coating layer process and uses a plasma treatment to remove contamination by a resist.

Sincerely,



Stephen B. Ackerman, Reg. #37761

2812

U. S. PATENT DOCUMENTS

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

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DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.